

In the Specification:

Please replace the paragraph beginning on page 12, line 6, with the following
amended paragraph:

Next, in the step of FIG.3G, an ion milling process is applied to the structure of FIG.3F while using ~~Ar ions~~ Ar ions 144 impinging in the direction generally perpendicularly to the substrate 101 for several seconds, and the exposed part of the Au protective film 110 is removed. As a result of removal of the low-resistance Au protective film from the region between the electrodes 117A and 117B, the shunt current path of the sensing current is eliminated.